

Title (en)
METAL MASK MATERIAL AND PRODUCTION METHOD THEREFOR

Title (de)
METALLMASKENMATERIAL UND HERSTELLUNGSVERFAHREN DAFÜR

Title (fr)
MATÉRIAU POUR MASQUE MÉTALLIQUE, ET PROCÉDÉ DE FABRICATION DE CELUI-CI

Publication
EP 3508285 B1 20210929 (EN)

Application
EP 17846646 A 20170831

Priority
• JP 2016169881 A 20160831
• JP 2017031349 W 20170831

Abstract (en)
[origin: EP3508285A1] Provided are: a metal mask material the shape change of which after etching is suppressed and which is preferable in order to achieve good resist adhesiveness and good etching workability; and a production method for the metal mask material. The metal mask material has a surface roughness in the rolling direction and a surface roughness in a direction perpendicular to the rolling direction, which satisfy $0.05 \mu\text{m} \leq \text{Ra} \leq 0.25 \mu\text{m}$ and $\text{Rz} \leq 1.5 \mu\text{m}$. The metal mask material has a skewness Rsk of 0 or greater in the direction perpendicular to the rolling direction. When a sample having a length of 150 mm and a width of 30 mm is cut out of the metal mask material and the thickness of the sample is reduced by 60% by etching from one side of the sample, the amount of warpage of the sample is 15 mm or less. The metal mask material has a thickness of 0.10-0.5 mm.

IPC 8 full level
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Cited by
EP3805415A1; EP4163407A1

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